

Form PT 01-449 (2001 Edition) Information Disclosure Statement BY APPLICANT (Use several sheets if necessary)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	Attorney Docket Number TEGL-01071US3	Serial/Patent Number 09/880,584
	Applicant/Patent Owner Stephen P. DeOrnellas		
	Filing/Issue Date June 13, 2001	Group Art Unit 1763	

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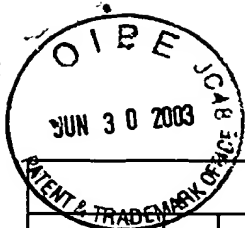
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U.S. PATENT PUBLICATIONS

Examiner Initial		Patent Application Publication Number	Publication Date	Applicant

PENDING U.S. PATENT APPLICATIONS

Examiner Initial		Application Number	Filing Date	First Named Inventor	Petition to Expunge? Yes No



FOREIGN PATENT DOCUMENTS

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						Yes	No
	JP-7-130712 /	5/19/1995	Japan				

OTHER DOCUMENTS (Include author (if any), title, publisher and place of publication, date and pertinent pages)

GAG	Ohno, et al. <i>Reactive Ion Etching of Cooper Films in SiCl₄ and N₂</i> , Japanese Journal of Applied Physics, Vol. 28, No. 6, June 1978, pp. 11070-1072 /
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Examiner

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